

Microelectronic Processing and Fabrication



Łukasiewicz

Institute of Microelectronics
and Photonics



We offer

- ✓ Performing individual technological steps or process sequences to fabricate microelectronic, optoelectronic and photonic devices
- ✓ Lithography, plasma etching, thin film deposition ion implantation, RTP (rapid thermal processing)
- ✓ Master and working stamp fabrication
- ✓ Performing UV-NIL (ultraviolet nanoimprint lithography) and Hot Embossing processes
- ✓ Photolithography mask: design and fabrication

Applications



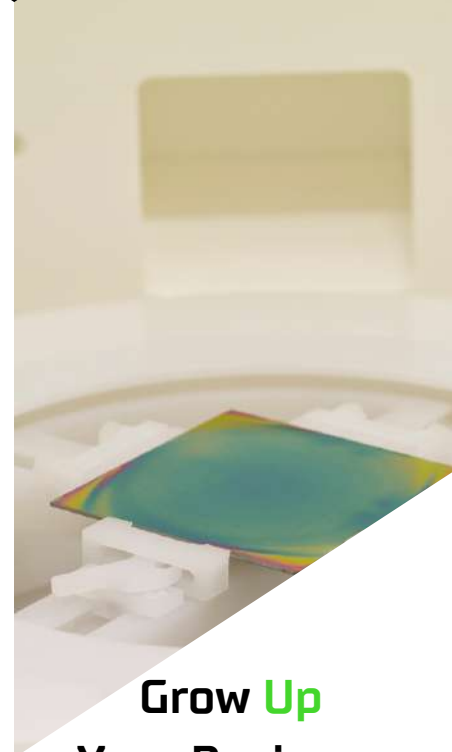
Optoelectronic and photonic devices: LED, LD, VCSEL,
optical fiber sensors



Microelectronic devices: Transistors (HEMTs,
MOSFET) and Diodes (Schottky)

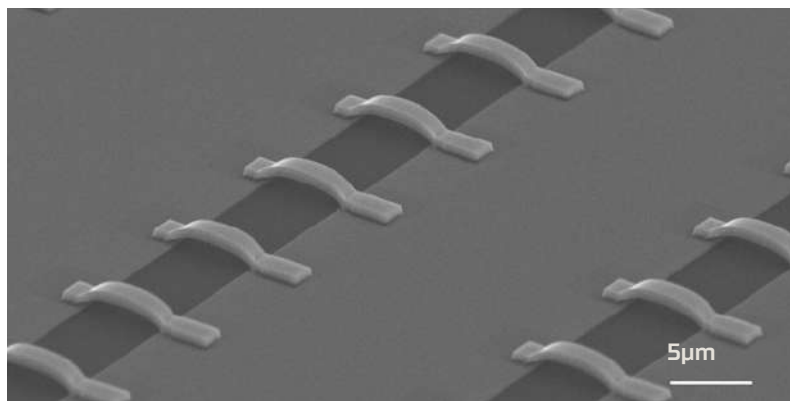
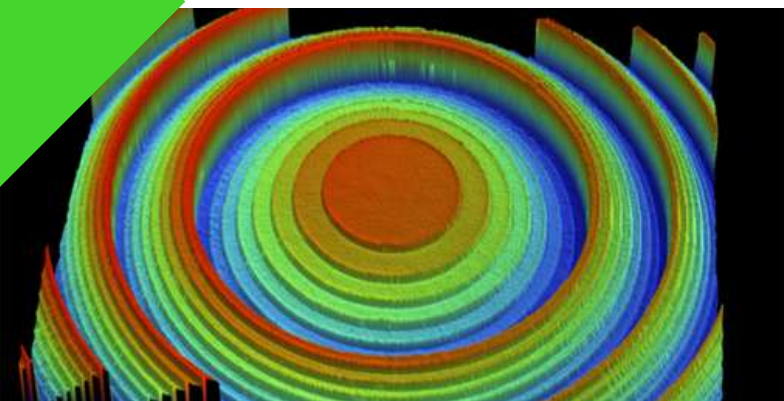
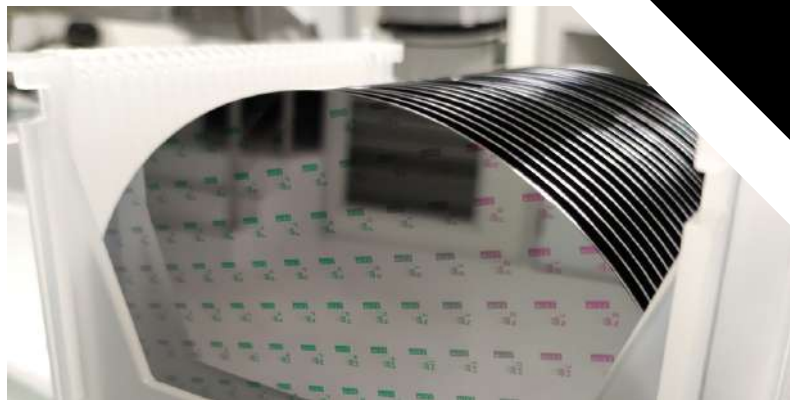
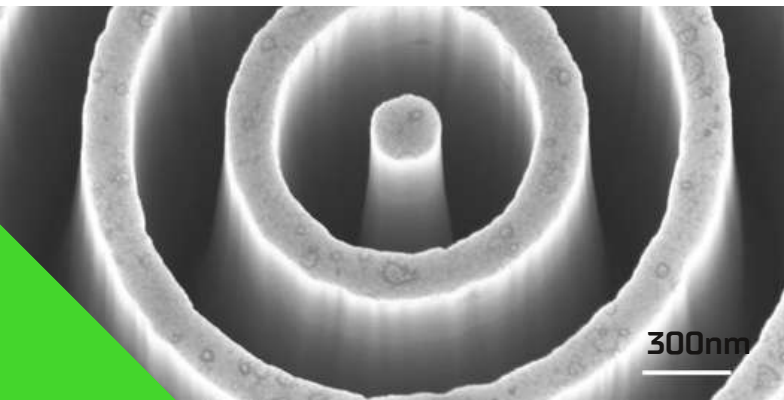


**ELECTRON BEAM LITHOGRAPHY
DUV PHOTOLITHOGRAPHY
DIRECT LASER WRITING
LITHOGRAPHY
NANOIMPRINT
PLASMA ETCHING**



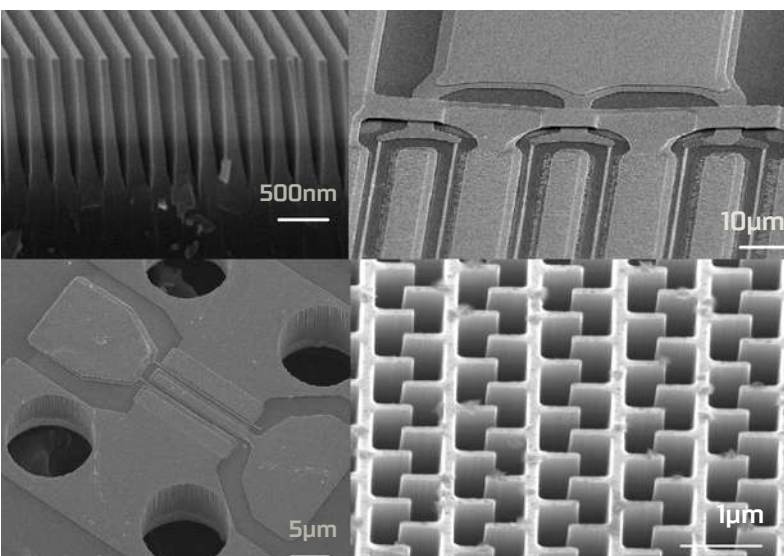
**Grow Up
Your Business
With Us**

Micro- and nano-3D structures



Photonic crystals for LED technology

T-gate, air bridge, via holes for HEMTs



Diffractive optical elements

- Single microlens and arrays [spherical, cylindrical, elliptical]
- Diffraction gratings, fan-out elements
- Computer generated holograms
- Apodised diffractive elements



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